

**OPTICAL PROXIMITY CORRECTION (OPC) TECHNIQUE USING  
GENERALIZED FIGURE OF MERIT FOR PHOTOLITHOGRAPHIC  
PROCESSING**

**ABSTRACT OF THE DISCLOSURE**

5           A method and associated computer program for making optical proximity  
corrections for a reticle layout topology. Edge segments of the reticle layout  
topology are manipulated to generate a corrected reticle layout accounting for  
optical distortions and, based on the corrected reticle layout, a plurality of  
individual figure of merit values are generated. A generalized figure of merit  
10 (GFOM) using the plurality of individual figure of merit values is then generated.

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